

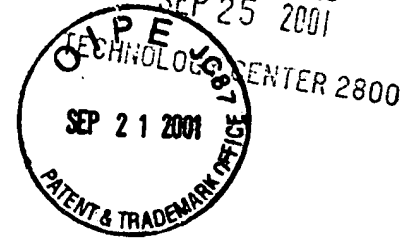
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ted A. Loxley
Serial No. : 09/490,162
Filed : January 22, 2000

For: PROCESS AND APPARATUS FOR CLEANING SILICON WAFERS

Examiner : V. Simkovic
Group Art Unit : 2812

Box Non-Fee Amendment
Assistant Commissioner for Patents
Washington, D.C. 20231



A M E N D M E N T

Sir:

In response to the Office action of May 23, 2001,
please amend the above-identified application as follows:

Cancel claim 27.

Add the following new claim:

30.
31. A process according to claim 18 wherein a row
of 10 or more silicon wafers is supported in a vessel or wafer
carrier during the cleaning operations, the front face of each
wafer being charged to a limited negative voltage, such as 2 to
60 volts, insufficient to harm the delicate microcircuits formed
on that face and having a field intensity of at least 0.02
volts/mm sufficient to cause efficient removal of harmful sub
0.05-micro particles. *vt*